

## IN THE CLAIMS

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1-21 (canceled)

22. (currently amended) A method ~~Method~~ for sputter-induced deposition of metal oxide layers on substrates by means of a reactive sputtering process, ~~wherein~~ comprising supplying an electrical output ~~is supplied to the~~ a plasma discharge acting on the sputter target to be deposited ~~sprayed~~ by means of at least two electrodes arranged adjacent to one another in ~~the~~ a plasma reaction space, which output is selected such that the metal oxide layers to be deposited on the substrate to be coated are deposited at a layer growth rate of  $\geq 4$  nm/s, the substrate to be coated being arranged during the coating process stationary in relation to ~~the~~ a target material to be sprayed, and in which the electrodes are connected electrically conductively to the outputs of an alternating current source, the alternating frequency of the alternating voltage envisaged for the electrical supply to the plasma discharge being chosen between 10 kHz and 80 kHz.

B6 23. (currently amended) ~~Method~~ A method for sputter-induced deposition of metal oxide layers on substrates by means of a reactive sputtering process, wherein the oxide layers to be deposited on the substrate to be coated are deposited at a layer growth rate of  $\geq 40$  nm m/min, ~~the~~ a substrate to be coated being moved along in front of ~~the~~ a target material to be deposited ~~sprayed~~, and in which ~~the~~ electrodes are connected electrically conductively to the outputs of an alternating current source, the alternating frequency of the alternating voltage ~~envisaged for the electrical supply~~ supplied to the plasma discharge being ~~chosen~~ between 10 kHz and 80 kHz.

Claims 24-26 (canceled)

Claim 27 (new) The method of claim 22, wherein the metal oxide layer is smooth.

Claim 28 (new) The method of claim 23, wherein the metal oxide layer is smooth.

Claim 29. (new) The method of claim 27, wherein the metal oxide layer is of a high optical quality.

Claim 30. (new) The method of claim 28, wherein the metal oxide layer is of a high optical quality.

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